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12/19/01

PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPLICATION

FILING DATE

CLASS

SUBCLASS

GAU

J2673
APPL NUM
10025085

FILING DATE
12/19/2001

CLASS
438

SUBCLASS
636

GAU
2813
2842

EXAMINER

T. Pham

**APPLICANTS: Tan Cher; Mukherjee-Roy Moitreyee; Foo Pang;

**CONTINUING DATA VERIFIED:

** FOREIGN APPLICATIONS VERIFIED:

SINGAPORE 200105179-6 08/24/2001

PG-PUB	DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>	ATTORNEY DOCKET NO
Foreign priority claimed 35 USC 119 conditions met Verified and Acknowledged Examiners's initials		<input type="checkbox"/> yes <input type="checkbox"/> no <input type="checkbox"/> yes <input type="checkbox"/> no	2085-00600 (IME-P002US)
TITLE : Method for preventing photoresist poisoning in semiconductor fabrication U.S.DEP'T. OF COMMERCE & TM-PTO-436L(Rev. 12-94)			

NOTICE OF ALLOWANCE MAILED

ISSUE FEE

Amount Due Date Paid

TERMINAL

DISCLAIMER

Assistant Examiner

CLAIMS ALLOWED

Total Claims

Print Claim for
O.G.

DRAWING

Sheets Drwg.

Figs. Drwg.

Print Fig.

Primary Examiner

Application Examiner

PREPARED FOR ISSUE
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